

7th spanish workshop in nanolithography

2017 **23-25**
oct
monday-wednesday

The 7th Spanish Workshop on Nanolithography (NANOLITO 2017) is a meeting focused on the research and applications of nanolithography performed at the Spanish-based institutions. As previous **Nanolito** workshops, this meeting aims to provide the right setting for technological discussions and sharing of ideas to encourage interregional scientific cooperation and to explore avenues for partnerships and commercialization.

INVITED SPEAKERS

Juergen Brugger, EPFL Switzerland
Philip Moll, Dresden Max-Planck-Institute for
 Chemical Physics of Solids
Armin W. Knoll, IBM Zurich
Thomas Bastuck, Fraunhofer Institute for
 Production Technology IPT Germany
Helmut Schiff, Paul Scherrer Institute

TOPICS:

- Electron-beam lithography
- Ion-beam lithography
- Electron-beam & ion-beam induced deposition /processing
- Nanoimprint and soft lithography
- Local probe lithography
- Self assembly
- Physical and chemical devices
- Industrial applications using nanolithography

There will be oral and poster contributions
 Registration fee: 100€ (includes lunch and conference dinner)
 Abstract submission dead line : **07 July, 2017**
 Abstract submission: nanolito2017@imdea.org
 More Information at: <http://nanoscience.imdea.org/nanolito>

NANOLITO SCIENTIFIC COMMITTEE

José María De Teresa (ICMA), Francesc Pérez-Murano (CNM), Albert Romano (UB), Ricardo García (IMM, CSIC), Santos Merino (Tekniker), José Ignacio Martín (UNIOVI), Soraya Sangiao (INA), Luis Hueso (CIC nanoGUNE), José Luis Vicent (UCM), Clivia Sotomayor (ICN), José Luis Prieto (UPM-ISOM), Isabel Rodríguez (IMDEA Nanoscience), Daniel Granados (IMDEA Nanoscience)

LOCAL ORGANIZING COMMITTEE

Isabel Rodríguez, Daniel Granados, Jose Luis Vicent, Jose Luis Prieto, Manuel Rodríguez, Jaime Hernández, Ivan Navarro, Fernando Jiménez, Maria Jesús Villa, Bonifacio Vega.

VENUE:

IMDEA Nanociencia
 c/ Faraday, 9 . Ciudad Universitaria de
 Cantoblanco. 28049 Madrid

